
Graphenea's New Product Fulfills Wafer-scale Integration Requirements

2020-01-01

Graphenea, a private European company producing high-quality graphene for industrial applications, has recently launched its new product: highly flat monolayer graphene grown on a copper thin film placed on a two-inch sapphire substrate. The roughness of this monolayer is reported to be less than 4 nm, which makes it particularly suitable for use in photonics, high-performance electronics, magnetic memory, and freestanding membranes.

[Graphenea](#) has announced the launch of a new product – highly flat monolayer graphene. The graphene is grown by CVD on copper thin film on a 2" sapphire substrate. With extremely low roughness that is less than 4 nm, this new product is targeted at applications in photonics, high-performance electronics, magnetic memory, and freestanding membranes.



The product aims to meet wafer-scale integration requirements to build uniform graphene devices in a fashion compatible with current industrial fabrication methods. The flat graphene product is ready to be transferred by electrochemical delamination or dry methods since the sapphire substrate is robust enough to withstand mechanical damage, preventing tearing and wrinkling of the thin Cu sheet. The total wafer thickness is 430 micrometers. Full product information can be found in Graphenea's online store.

Read the [original article](#) on Graphenea.